

## Posters

## GENERAL INFRASTRUCTURE

G 1	<p><b>Establishing a nano metrology facility in South Africa</b>  O. Kruger, L. Mostert  NMISA South Africa, Bld 5, CSIR campus, Brumeria, Private Bag X34, 0001 Pretoria, South Africa</p>
G 2	<p><b>European project on metrology for manufacturing 3D stacked integrated Circuits</b>  D. Allal 1), F. Piquemal 1), A. Delvallée 1), F. Ziadé 1), B. Pollakowski 2), A. Cuenat 3)  1) Laboratoire National de Métrologie et d'Essais (LNE), 29 av. Roger Hennequin , 79197 Trappes Cedex, France  2) Physikalisch-Technische Bundesanstalt (PTB), Abbestr. 2-12, 10587 Berlin, Germany  3) National Physical Laboratory (NPL), Hampton Road, Teddington, Middlesex, TW11 LW, United Kingdom</p>
G 3	<p><b>Club nanoMétrologie: a French initiative in networking industrial and academic sectors on metrology for nanotechnology and nanoscience</b>  F. Piquemal 1), G. Favre 1), J. Carimalo 2)  1) Laboratoire National de Métrologie et d'Essais (LNE), 29 av. Roger Hennequin , 79197 Trappes Cedex, France  2) CNRS – Institut de Physique, 3, rue Michel Ange, 75794 Paris Cedex 16, France</p>
G 4	<p><b>Intercomparison on AFM and SEM measurements of 2D gratings organized in the frame of the French nanometrology club</b>  S. Ducourtieux, A. Delvallée  Laboratoire national de métrologie et d'essais (LNE), 29 avenue Roger Hennequin, 79197 Trappes Cedex, France</p>
G 5	<p><b>Study of user influence in routine SPM data processing</b>  David Nečas 1), Petr Klapetek 2)  1) Central European Institute of Technology, Žerotínovo nám. 617/9, 601 77 Brno, Czech Republic  2) Czech Metrology Institute (CMI), Okružní 31, 638 00 Brno, Czech Republic</p>
G 6	<p><b>Fast SPM data simulations based on graphics card use</b>  Jan Martinek, Petr Klapetek  Czech Metrology Institute (CMI), Okružní 31, 638 00 Brno, Czech Republic</p>

# INSTRUMENTATION

I 01	<p><b>Recent advances in the development of the LNE metrological AFM</b>  Y.Boukellal, S. Ducourtieux, P. Ceria, J. Song  Laboratoire National de Métrologie et d'Essais (LNE), 29 avenue Roger Hennequin, 78190 Trappes Cedex, France</p>
I 02	<p><b>Displacement sensor calibration uncertainty with Fabry-Perot interferometry</b>  D. Voigt, A.S. van de Nes, S.A. van den Berg, R.H. Bergmans  VSL Dutch Metrology Institute, Thijseweg 11, 2629 JA Delft, The Netherlands</p>
I 03	<p><b>DBR diode based laser source working at 633 nm for dimensional nano-metrology</b>  S. Rerucha 1), T. M. Pham 1), M. Cizek 1), V. Hucl 1), J. Lazar 1), O. Cip 1), A. Yacoot 2)  1) Institute of Scientific Instruments of the Czech Academy of Sciences (ISI), Kralovopolska 147, 612 64 Brno, CZ  2) National Physical Laboratory (NPL), Hampton Road, Teddington, Middlesex, TW11 0LW, UK</p>
I 04	<p><b>Improvement in metrological AFM for long distance measurements</b>  N. Vorbringer-Dorozhovets, E. Manske  TU Ilmenau, P.O. Box 100565, Ehrenbergstr. 29 EAZ, 98693 Ilmenau, Germany</p>
I 05	<p><b>Nanopositioning &amp; nanomeasuring technology –following the challenges of nanofabrication</b>  Eberhard Manske 1), Tino Hausotte 2)  1) Institute of Process Measurement and Sensor Technology, TU Ilmenau, PF 100565, D-98684 Ilmenau, Germany  2) Institute of Manufacturing Metrology (FMT), Friedrich-Alexander-Universität Erlangen-Nürnberg (FAU),  Nägelsbachstraße 25, 91052 Erlangen, Germany</p>
I 06	<p><b>Piezo-Resistive Sensing Active (PRSA) Probes integrated into a Nanomeasuring Machine (NMM-1)</b>  Ahmed El Melegy 1+3), Tino Hausotte 1), Mohammad Abd El-wahed Younes 2), Mohammed Amer 3)  1) Institute of Manufacturing Metrology (FMT), Friedrich-Alexander-Universität Erlangen-Nürnberg (FAU),  Nägelsbachstraße 25, 91052 Erlangen, Germany  2) Faculty of Engineering, Alexandria University, Alexandria, Egypt  3) National Institute for Standard (NIS), Tersa Street, El Haram, El Giza, Egypt</p>
I 07	<p><b>Development of a long-travel nanopositioning air bearing stage</b>  P. Sosinowski  Central Office of Measures, Length and Angle Department, ul. Elektoralna 2, 00-139 Warsaw, Poland</p>
I 08	<p><b>The Design and Performance of Metrology Scanning Probe Microscope Based on Six Axis Interferometric Measurements</b>  M. Valtr 1), V. Hortvík 1), P. Klapetek 1), J. Lazar 2), O. Číp 2), J. Hrabina 2), M. Holá 2), M. Šerý 2)  1) Czech Metrology Institute (CMI), Okružní 31, 638 00 Brno, Czech Republic  2) Institute of Scientific Instruments, Academy of Sciences, Královopolská 147, 612 64 Brno, Czech Republic</p>
I 09	<p><b>Drift free and precise setup for low load force contact atomic force microscopy with piezoresistive deflection probes</b>  P. Biczysko, A. Dzierka, G. Jozwiak, M. Rudek and T. Gotszalk  Wroclaw University of Technology, Faculty of Microsystem Electronics and Photonics,  ul. Janiszewskiego 11/17, 50-372 Wroclaw, Poland</p>
I 10	<p><b>FIB-SEM integrated SIMS-AFM for 3D local elemental mapping</b>  L. Pillatsch, J. Whitby, I. Utke, J. Michler  EMPA, Swiss Federal Institute of Materials Testing and Research, Feuerwerkerstrasse 39, 3602 Thun, Switzerland</p>
I 11	<p><b>Detection principles based on new detector technology and parameters</b>  Y. Akinay  Iron and Steel Institute, University of Karabuk, Turkey</p>

## APPLICATION – SPECIAL SPM MODES

A 01	<p><b>SEM based electro-optical characterization of core-shell LEDs and simulation of parasitic contributions in CL and EBIC imaging</b></p> <p>J. Ledig 1), C. G. Frase 2), J. Hartmann 1), A. Ludwigs 1), H.-H. Wehmann 1), A. Waag 1)</p> <p>1) Institut für Halbleitertechnik &amp; Laboratory for Emerging Nanometrology, Technische Universität Braunschweig, Hans-Sommer-Str. 66, 38106 Braunschweig, Germany</p> <p>2) Physikalisch-Technische Bundesanstalt (PTB), Bundesallee 100, 38116 Braunschweig, Germany</p>
A 02	<p><b>Scanning Microwave Microscopy characterization of multi-junction solar cells</b></p> <p>A. Delvallée 1), F. Piquemal 1), A. Bounouh 1), K. Louarn 1), G. Almuneau 2)</p> <p>1) Laboratoire National de métrologie et d'Essais (LNE), 29 av. Roger Hennequin, 78197 Trappes Cedex, France</p> <p>2) Laboratoire d'Analyse et d'Architecture des Systèmes (LAAS-CNRS), 7 av. du Colonel Roche, 31400 Toulouse, FR</p>
A 03	<p><b>Contrast enhancement in wide-field Kerr microscopy on soft magnetic films</b></p> <p>G. Büttel, J. Joppich, T. Karwoth, U. Hartmann</p> <p>Institute of Experimental Physics, Saarland University, 66123 Saarbrücken, Germany</p>
A 04	<p><b>Wide-field fluorescence microscopy for detection of biochemical processes in real time</b></p> <p>M. Szalkowski 1), D. Kowalska 1), S. Maćkowski 1), J. D. J. Olmos 2), J. Kargul 2), S. Maćkowski 3)</p> <p>1) Institute of Physics, Faculty of Physics, Astronomy and Informatics, Nicolaus Copernicus University, Grudziadzka 5, 87-100 Torun, Poland</p> <p>2) Center of New Technologies, University of Warsaw, Banacha 2C, 02-097 Warsaw, Poland</p> <p>3) Wrocław Research Center EIT+, Stabłowicka 147, Wrocław, Poland</p>
A 05	<p><b>Multi-resonance Kelvin Probe Force Microscopy &amp; quantitative assessment of image quality</b></p> <p>D. Kopiec, G. Jóźwiak, M. Rudek, T. Gotszalk</p> <p>Faculty of Microsystem Electronics and Photonics, Wrocław University of Technology, Janiszewskiego 11/17, Wrocław 50-372, Poland</p>
A 06	<p><b>QUANTIHEAT Project: Identity, objectives and first results</b></p> <p>S. Gomès 1), QUANTIHEAT consortium 2)</p> <p>1) Université de Lyon, CNRS, INSA de Lyon, CETHIL, UMR5008, 69621, Villeurbanne, France</p> <p>2) dto. / Univ. of Lancaster, UK / Kelvin NanoTechnology, UK / LNE, FR / Glasgow Univ., UK / VTT, FI / NPL, UK / THALES R&amp;T, FR / CMI, CZ / PICOSUN Oy, Finland / Ecole Polytech. Féd. Lausanne, CH / Fundació Privada Institut Català de Nanotec., ES / Univ. de Reims Champagne-Ardenne, FR / Ecole Sup. de Physique et de Chimie Ind. Paris, FR / Micro Resist Technology GmbH, DE / Ecole Nat. Sup. de Mécanique et des Microtech., FR / Berliner NANOTEST&amp;Design GmbH, DE / CONPART As, NO / NT-MDT Europe B.V., NL / Univ. Paris Descartes, FR</p>
A 07	<p><b>Heat Transfer Mechanisms Quantified at Submicron Scales in Scanning Thermal Microscopy</b></p> <p>S. Gomès 1), A. Assy 2)</p> <p>1) Université de Lyon, CNRS, INSA de Lyon, CETHIL, UMR5008, F-69621, Villeurbanne, France</p> <p>2) LPEM, UMR CNRS 8213, ESPCI, Paris, France</p>
A 08	<p><b>Localized nanosize heat source for investigation of thermal expansion of nanostructures</b></p> <p>Maciej Rudek 1), Piotr Kunicki 1), Teodor Gotszalk 1), Paweł Janus 2), Piotr Grabiec 2), Andrzej Sierakowski 2)</p> <p>1) Wrocław University of Technology, Faculty of Microsystem Electronics and Photonics, ul. Janiszewskiego 11/17, 50-372 Wrocław, Poland</p> <p>2) Instytut Technologii Elektronowej al. Lotników 32/46, Warszawa, Poland</p>
A 09	<p><b>Thermal nanometrology using piezoresistive SThM probes with metallic tips</b></p> <p>Paweł Janus 1), Andrzej Sierakowski 1), Piotr Grabiec 1), Maciej Rudek 2), Piotr Kunicki 2), Andrzej Dzierka 2), Paweł Biczysko 2), Grzegorz Jóźwiak 2), Teodor Gotszalk 2)</p> <p>1) Instytut Technologii Elektronowej al. Lotników 32/46, Warszawa, Poland</p> <p>2) Wrocław University of Technology, Faculty of Microsystem Electronics and Photonics, ul. Janiszewskiego 11/17, 50-372 Wrocław, Poland</p>
A 10	<p><b>Tunneling Junction Simulation Environment for the metrological characterization of scanning probe controllers</b></p> <p>K. Gajewski, T. Piasecki, D. Kopiec, T. Gotszalk</p> <p>Wrocław University of Technology, Faculty of Microsystem Electronics and Photonics, Janiszewskiego 11/17, 50-372 Wrocław, Poland</p>

## APPLICATION – ROUGHNESS, TIP SHAPE

A 11	<p><b>Surface texture measurements of a polished silicon wafer by AFM, optical PSI and stylus-profilometry</b>  R. Bellotti, G.B. Picotto  Istituto Nazionale di Ricerca Metrologica (INRIM), Strada delle Cacce 91, 10135 Torino, Italy</p>
A 12	<p><b>The roughness changes improvement analysis of the non-uniform surfaces investigated by means of atomic force microscopy with scanning area positioning aided with nanomarkers</b>  A. Sikora  Electrotechnical Institute Division of Electrotechnology and Materials Science,  M. Skłodowskiej-Curie 55/61 50-369 Wrocław, Poland</p>
A 13	<p><b>Flexible fabrication of defined scalable roughness structures with Focused Ion Beam (FIB)</b>  M. Hemmleb 1), D. Berger 2), T. Dziomba 3), P. Krebs 3), A. Felgner 3), H.-U. Danzebrink 3), L. Koenders 3)  1) m2c calibration, Alt Nowawes 83a, 14482 Potsdam, Germany  2) Technische Universität Berlin, ZE Elektronenmikroskopie, Straße des 17. Juni 135, 10623 Berlin, Germany  3) Physikalisch-Technische Bundesanstalt (PTB), Bundesallee 100, 38116 Braunschweig, Germany</p>
A 14	<p><b>The application of a piezoresistive cantilever microprobe with diamond tip on profile and roughness measurements</b>  Min Xu, Lutz Doering, Uwe Brand  Physikalisch-Technische Bundesanstalt (PTB), Bundesallee 100, 38116 Braunschweig, Germany</p>
A 15	<p><b>High speed micro probe for roughness measurements in high aspect ratio microstructures</b>  Lutz Doering 1), Uwe Brand 1), Erwin Peiner 2+3)  1) Physikalisch-Technische Bundesanstalt (PTB), Bundesallee 100, 38116 Braunschweig, Germany  2) Institut für Halbleitertechnik (IHT), TU Braunschweig, Braunschweig, Germany  3) Laboratory of Emerging Nanometrology (LENA), Braunschweig, Germany</p>
A 16	<p><b>Corrosion process monitoring by AFM higher harmonic imaging</b>  S. Babicz 1), J. Smulko 1), A. Zieliński 2), K. Darowicki 2)  1) Gdansk University of Technology, Faculty of Electronics, Telecommunications and Informatics, Department of Metrology and Optoelectronics, G. Narutowicza 11/12, 80-233 Gdańsk, Poland  2) Gdansk University of Technology, Chemistry Faculty, Department of Electrochemistry, Corrosion and Materials Engineering, G. Narutowicza 11/12, 80-233 Gdańsk, Poland</p>
A 17	<p><b>Characterisation of the growth of carboxyl-rich films with high roughness and aspect ratio</b>  D. Nečas 1), A. Obrusník 1), L. Zajíčková 1), P. Klapetek 2)  1) Plasma Technologies, CEITEC, Masaryk University, Kamenice 5, 62500 Brno, Czech Republic  2) Czech Metrology Institute (CMI), Okružní 31, 63800 Brno, Czech Republic</p>
A 18	<p><b>Virtual reference probe method for nanoscale morphology measurement</b>  H. Itoh  National Institute of Advanced Industrial Science and Technology Research (AIST),  1-1 Umezono 1-ChomeTsukuba-shi, Ibaraki-ken 305-8568 Japan</p>
A 19	<p><b>Tip shape measurements: calibration sample, noise reduction and blind tip reconstruction</b>  1) G. Jóźwiak 1), M. Moczala 1), K. Gajewski 1), T. Gotszalk 1), A. Sierakowski 2), P. Wójcicki 2)  1) Wrocław University of Technology, Faculty of Microsystem Electronics and Photonics,  ul. Janiszewskiego 11/17, 50-372 Wrocław, Poland  2) Institute of Electron Technology, Al. Lotników 32/46, 02-668 Warsaw, Poland</p>

## APPLICATION – NANOPARTICLES, PORES

A 20	<p><b>Design of experiment for uncertainty evaluation of nanoparticle diameter measurements with AFM</b></p> <p>B. De Boeck, J. Pétry, N. Sebaihi, M. Dobre SMD, FPS Economy, Koning Albert II-laan 16, 1000 Brussels, Belgium</p>
A 21	<p><b>Nanoparticle standards for extracellular vesicle measurements</b></p> <p>A. Nicholet and F. Meli Federal Institute of Metrology METAS, Lindenweg 50, CH-3003 Bern-Wabern, Switzerland</p>
A 22	<p><b>Simultaneous measurement of lateral and vertical size of nanoparticles using transmission scanning electron microscopy (TSEM)</b></p> <p>E. Buhr, D. Bergmann, P. Cizmar, C.G. Frase, M. Bug Physikalisch-Technische Bundesanstalt (PTB), Bundesallee 100, 38116 Braunschweig, Germany</p>
A 23	<p><b>Pore characterization of mesoporous silica particles synthesized using rice husk as a silicon source</b></p> <p>C. Vanichvattanadecha 1), W. Singhapong 2), A. Jaroenworuluck 1)</p> <p>1) National Metal and Materials Technology Center, National Science and Technology Development Agency, 114 Thailand Science Park, Phahonyothin Road, Khlong Nueng, Khlong Luang, Pathum Thani 12120, Thailand 2) Interdisciplinary Graduate Program in Advanced and Sustainable Environmental Engineering (TAIST-Tokyo Tech), Faculty of Engineering, Kasetsart University, Bangkok 10900, Thailand</p>

## APPLICATION – NANOMECHANICS, GRAPHENE

A 24	<p><b>Material point method for nanomechanical modelling</b></p> <p>R. Šlesinger Czech Metrology Institute (CMI), Okružní 31, 63800 Brno, Czech Republic</p>
A 25	<p><b>Relative humidity and the AFM: force-displacement adhesion measurements and atomistic molecular dynamics simulations at different humidity levels</b></p> <p>J. Seppä 1), V. Korpelainen 1), H. Husu 1), A. Lassila 1), B. Reischl 2)</p> <p>1) VTT Technical Research Centre of Finland Ltd, Centre for Metrology MIKES, P.O. Box 1000, 02044 VTT, Finland <i>H. Husu is currently affiliated with nLIGHT Finland, Sorronrinne 9, 08500 Lohja, Finland</i> 2) Curtin Institute for Computation, Nanochemistry Research Institute and Department of Chemistry Curtin University, GPO Box U1984, Perth, WA 6845, Australia</p>
A 26	<p><b>Comparative measurements of the spring constant of a soft cantilever using PTB's MEMS and nanonewton force facility</b></p> <p>S. Gao 1), D. Nies 1), V. Nesterov 1), U. Brand 1), O. Belai 2)</p> <p>1) Physikalisch-Technische Bundesanstalt (PTB), Bundesallee 100, 38116 Braunschweig, Germany 2) Institute of Automation and Electrometry, Koptjug Avenue 1, 630090 Novosibirsk, Russia</p>
A 27	<p><b>Determination of elastic properties of graphene membranes using the AFM-bending test</b></p> <p>Z. Li 1), U. Brand 1), F. Pohlenz 1), X.-H. Zhang 2), N. Wollschläger 3), P. Klapetek 4)</p> <p>1) Physikalisch-Technische Bundesanstalt (PTB), 38116 Braunschweig, Germany 2) Universität Bielefeld, 33615 Bielefeld, Germany 3) Bundesanstalt für Materialforschung und -prüfung (BAM), 12205 Berlin, Germany 4) Czech Metrology Institute (CMI), Okružni 3, 638 00 Brno, Czech Republic</p>
A 28	<p><b>AFM study on the surface morphology of SiC towards epitaxial graphene</b></p> <p>M. Kruskopf, K. Pierz, D. Momeni Pakdehi, T. Dziomba, F.J. Ahlers, H.W. Schumacher Physikalisch-Technische Bundesanstalt (PTB), Bundesallee 100, 38116 Braunschweig, Germany</p>

## STANDARDS

S 1	<p><b>Calibrating the AFM XY-magnification at Sub-nanometer Scale by Highly Ordered Pyrolytic Graphite</b></p> <p>Bo-Ching He, Wei-En Fu, Gwo-Jen Wu          Center for Measurement Standards (CMS), Industrial Technology Research Institute (ITRI),          No.321, Kuangfu Rd., Sec.2, Hsinchu, 30011, Taiwan</p>
S 2	<p><b>Determination of subwavelength grating structure geometry by hybrid analysis of optical scatterometry and ellipsometry</b></p> <p>M. Wurm 1), J. Endres 1), E. Agocs 1), J. Probst 2), M. Schoengen 2), A. Diener 1), B. Bodermann 1)          1) Physikalisch-Technische Bundesanstalt (PTB), Bundesallee 100, 38116 Braunschweig, Germany          2) Helmholtz-Zentrum Berlin für Materialien und Energie GmbH, Albert-Einstein-Str. 15, 12489 Berlin, Germany</p>
S 3	<p><b>Investigations of different scatterometric techniques for characterisation of 3-dimensional structures</b></p> <p>D. Bergmann 1), B. Bodermann 1), E. Buhr 1), A. Diener 1), J. Endres 1), M. Krumrey 1), F. Scholze 1),          V. Soltwisch 1), M. Wurm 1), S. Burger 2), B. P. Ng 3)          1) Physikalisch-Technische Bundesanstalt (PTB), Bundesallee 100, 38116 Braunschweig, Germany          2) JCMwave GmbH, Bolivarallee 22, 14050 Berlin, Germany          3) Singapore Institute of Manufacturing Technology, 71 Nanyang Drive, 638075 Singapore</p>
S 4	<p><b>Measurement accuracy analysis for surface microgeometry nano - standards with irregularity height/depth below 1 µm for 2D parameters</b></p> <p>A. Kapińska-Kiszko, A. Okrasa, M. Uściński, Ł. Ślusarski          Central Office of Measures (GUM), ul. Elektoralna 2, 00-139 Warszawa, Poland</p>
S 5	<p><b>Study of uncertainties of height measurements of monoatomic steps on Si 7×7 using DFT</b></p> <p>A. Charvatová Campbell 1), P. Klapetek 1), P. Jelinek 2)          1) Czech Metrology Institute (CMI), Okružní 31, 638 00 Brno, Czech Republic          2) Institute of Physics, Academy of Sciences of the Czech Republic, Cukrovarnická 10,          162 00 Prague, Czech Republic</p>
S 6	<p><b>New reference material for imaging XPS instrument characterization</b></p> <p>S. Bütefisch 1), T. Weimann 1), I. Busch 1), H.-U. Danzebrink 1), T. Gross 2), W. Unger 2), T. Wirth 2)          1) Physikalisch-Technische Bundesanstalt (PTB), Bundesallee 100, 38116 Braunschweig, Germany          2) Bundesanstalt für Materialforschung und -prüfung (BAM), Unter den Eichen 87, 12205 Berlin, Germany</p>

## POST-DEADLINE

PD 1	<p><b>Magnetolectric versus thermal actuation of piezoresistive shear-force AFM probes - results comparison</b></p> <p>A. Sierakowski 1), P. Janus 1), R. Dobrowolski 1), P. Grabiec1); D. Kopiec 2) , W. Majstrzyk 2), T. Gotszalk 2)</p> <p>1) Institute of Electron Technology ITE, al. Lotnikow 32/46, 02-668 Warsaw, Poland 2) Wroclaw University of Technology, Faculty of Microsystem Electronics and Photonics, ul. Janiszewskiego 11/17, 50-372 Wroclaw, Poland</p>
PD 2	<p><b>Design and evaluation of Precision Current Integrator for Scanning Probe Microscopy</b></p> <p>K. Raczkowski, T. Piasecki, M. Rudek, T. Gotszalk Wroclaw University of Technology, Faculty of Microsystem Electronics and Photonics, ul. Janiszewskiego 11/17, 50-372 Wroclaw, Poland</p>
PD 3	<p><b>DBR diode based laser source working at 633 nm for dimensional nano-metrology</b></p> <p>S. Rerucha 1), T. M. Pham 1), M. Cizek 1), V. Hucl 1), J. Lazar 1), O. Cip 1); A. Yacoot 2)</p> <p>1) Institute of Scientific Instruments of the Czech Academy of Sciences (ISI), Kralovopolska 147, 612 64 Brno, CZ 2) National Physical Laboratory (NPL), Hampton Road, Teddington, Middlesex, TW11 0LW, UK</p>
PD 4	<p><b>Coordinate interferometric measuring system for positioning of a sample in electron-beam writer</b></p> <p>M. Holá, M. Čížek, V. Hucl, Š. Řeřucha and J. Lazar Institute of Scientific Instruments, Academy of Sciences, Královopolská 147, 612 64 Brno, Czech Republic</p>
PD 5	<p><b>A combined SThM/SEM instrument for the investigation of influent parameters in nano-scale thermal contact</b></p> <p>S. Gomès 1), D. Renahy 1), F. Bouhacine 1); P. Vincent 2)</p> <p>1) Université de Lyon, Centre d'Énergétique et de Thermique de Lyon CETHIL-UMR5008, CNRS, INSA de Lyon, F-69621 Villeurbanne, France 2) Université de Lyon, Institut Lumière et Matière ILM-UMR5306, CNRS,F-69622 Villeurbanne, France</p> <p><i>This contribution was first listed as Talk 4.4, but then converted to a Post-Deadline Poster</i></p>
	<p><i>To be updated in due time</i></p>